

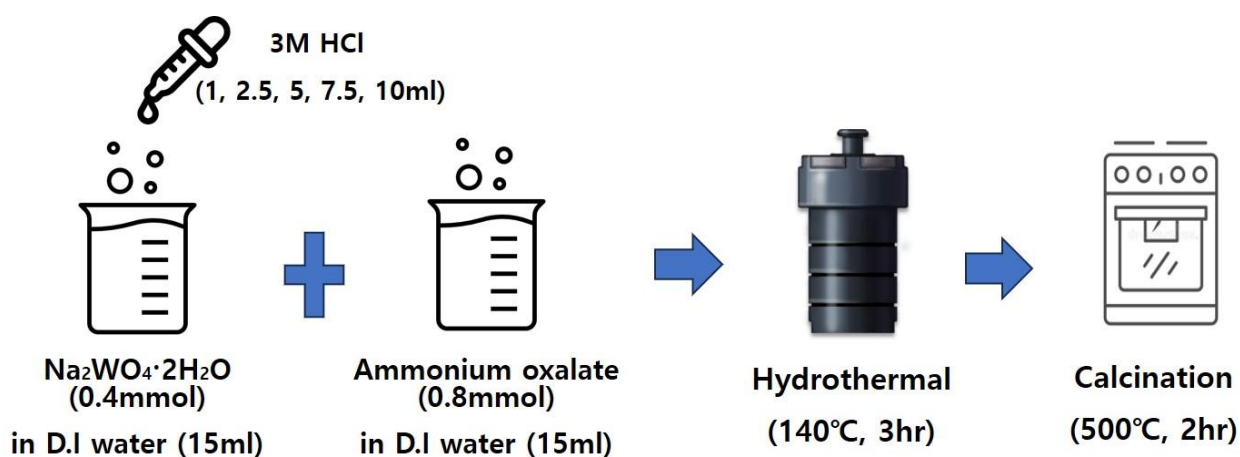
Supplementary Materials

# Controlled Growth of WO<sub>3</sub> Photoanode under Various pH Conditions for Efficient Photoelectrochemical Performance

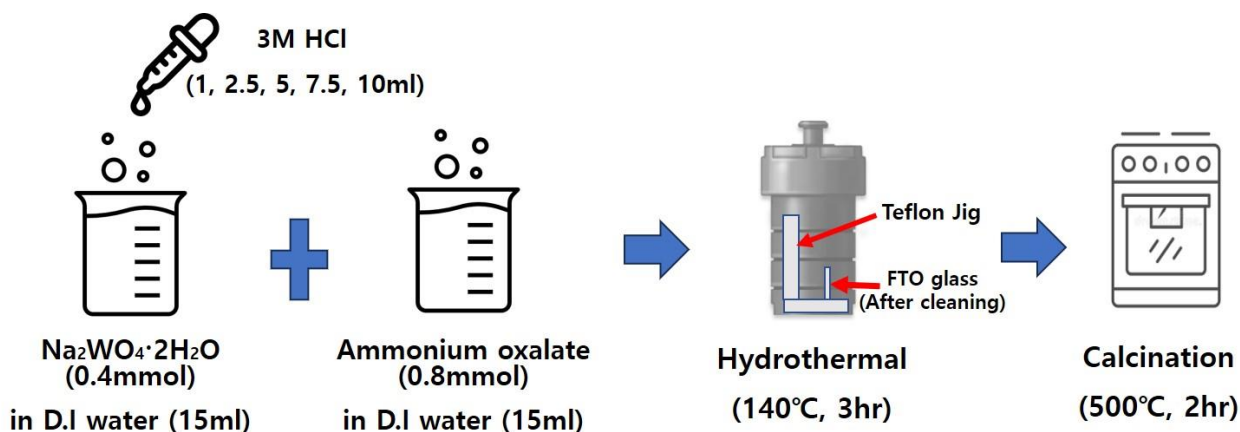
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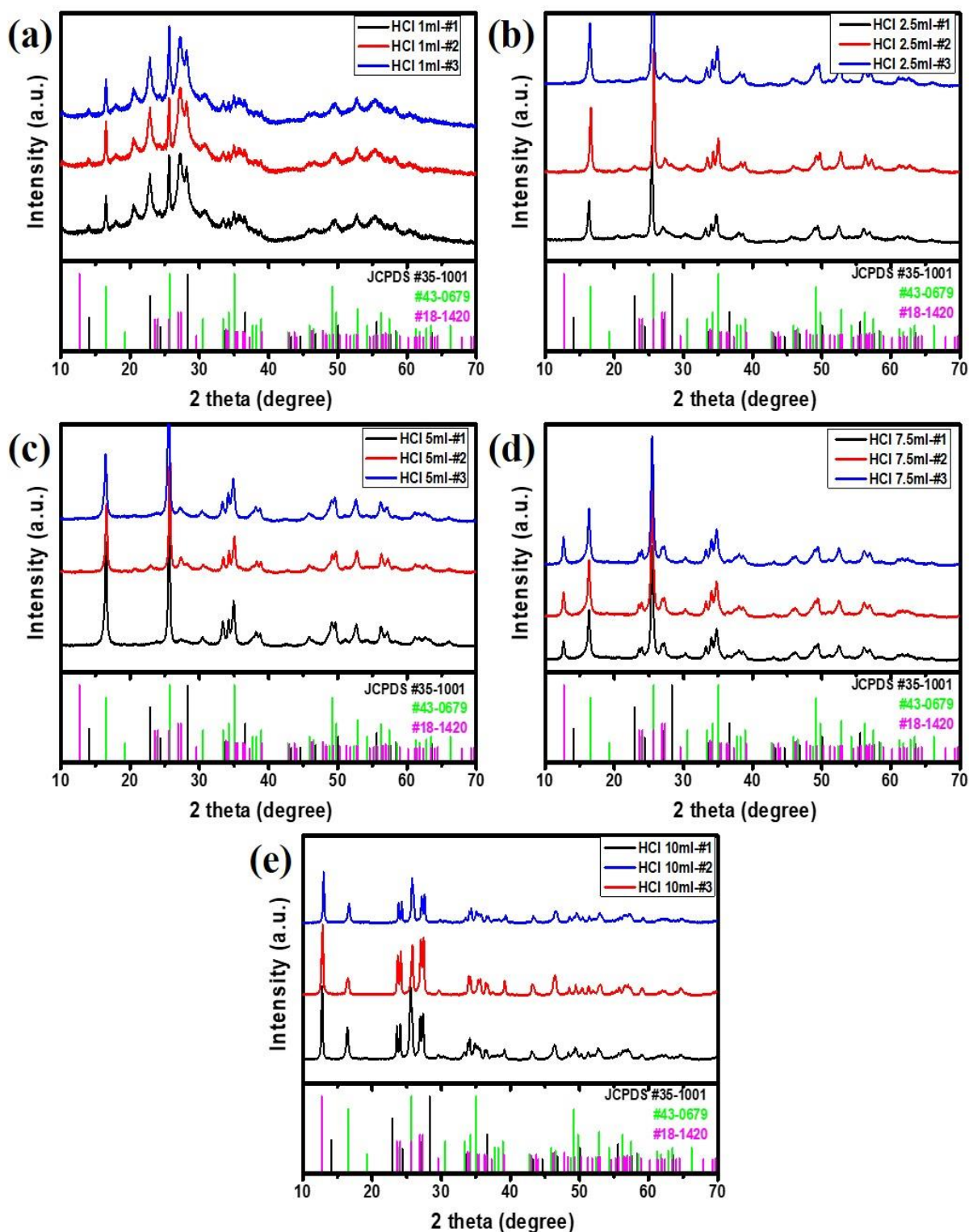
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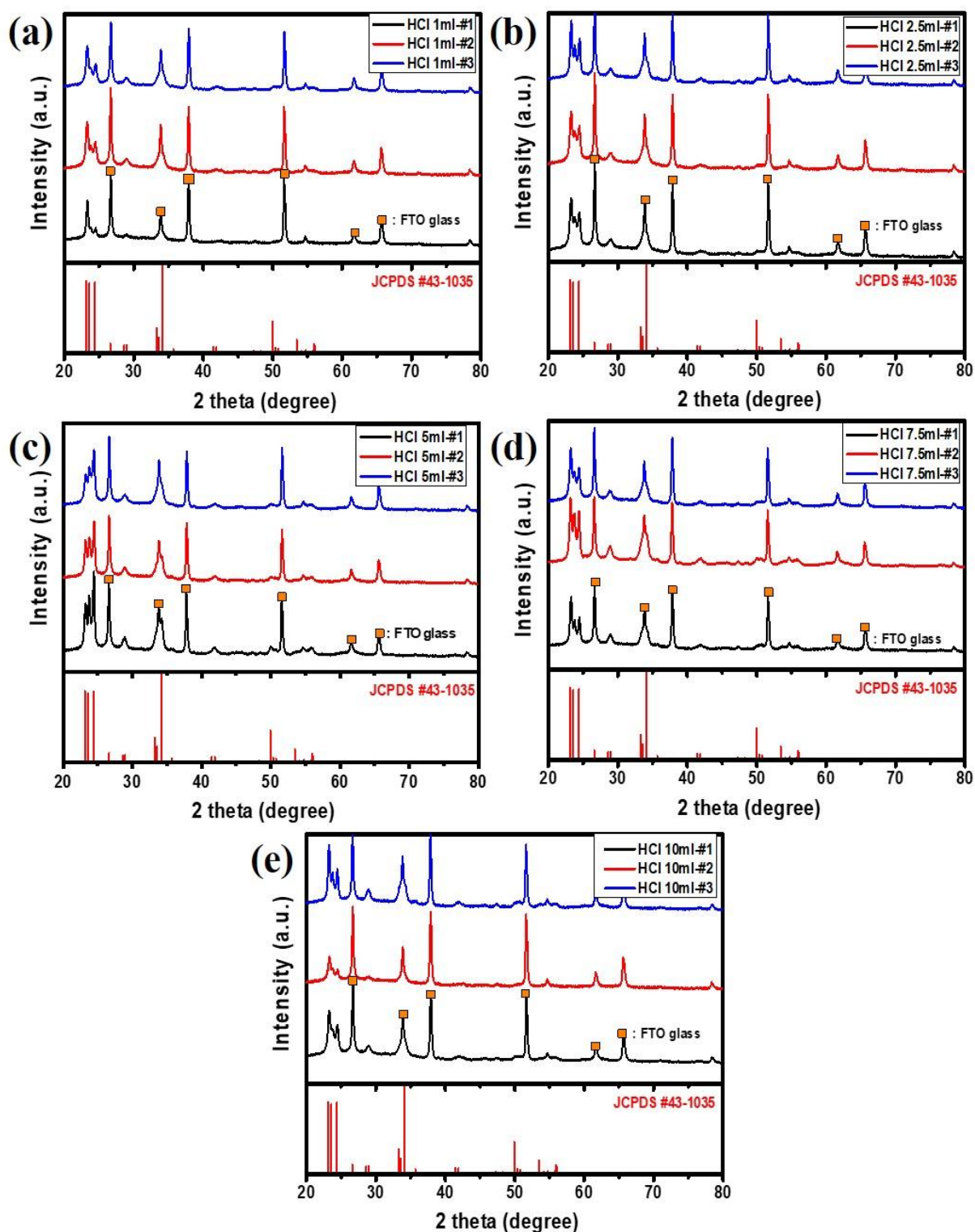
**Figure S1.** Schematics of the preparation procedures of WO<sub>3</sub>·nH<sub>2</sub>O and WO<sub>3</sub> materials.



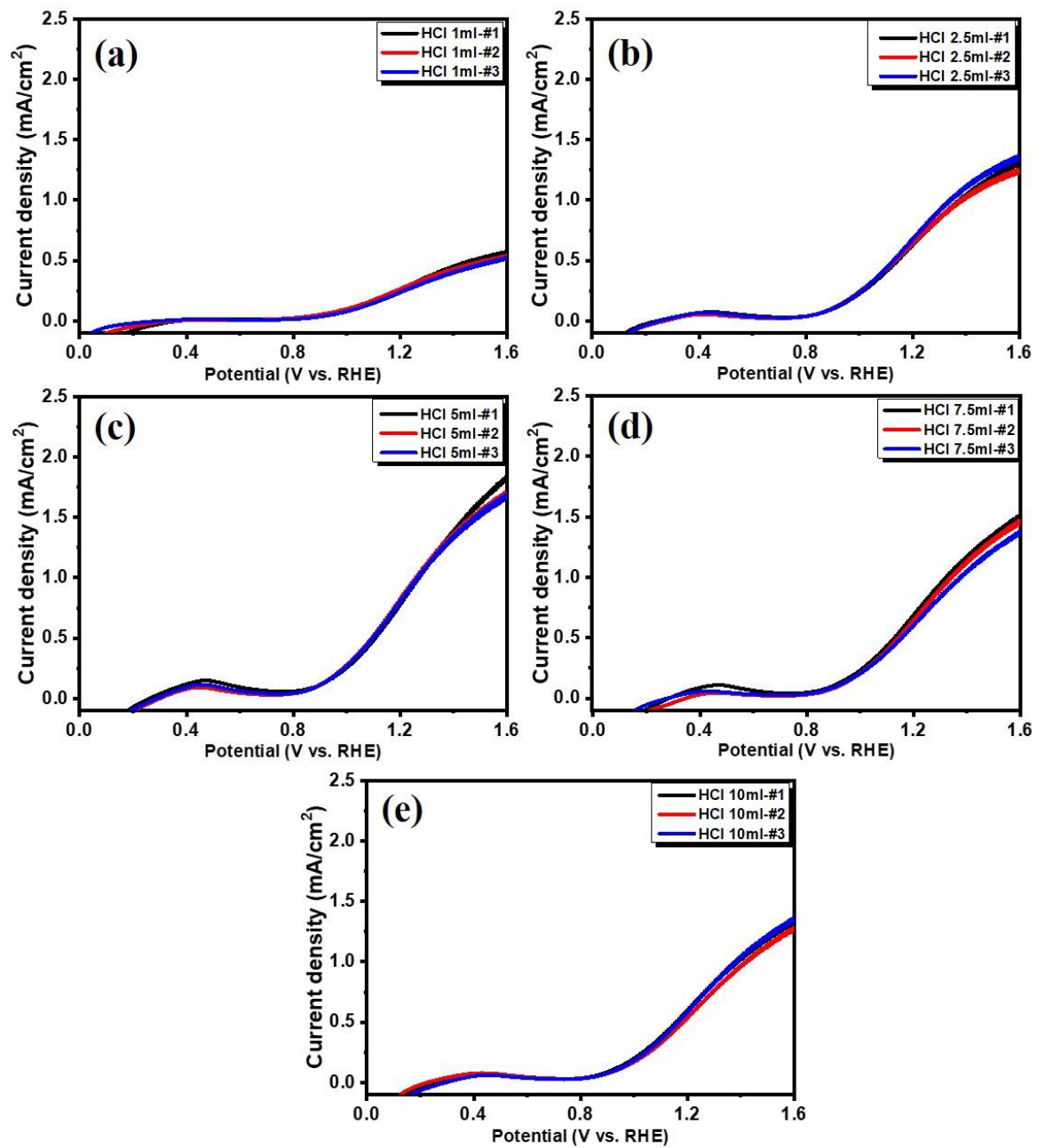
**Figure S2.** Illustrations of the preparation procedures of WO<sub>3</sub> photoanode on FTO substrate.



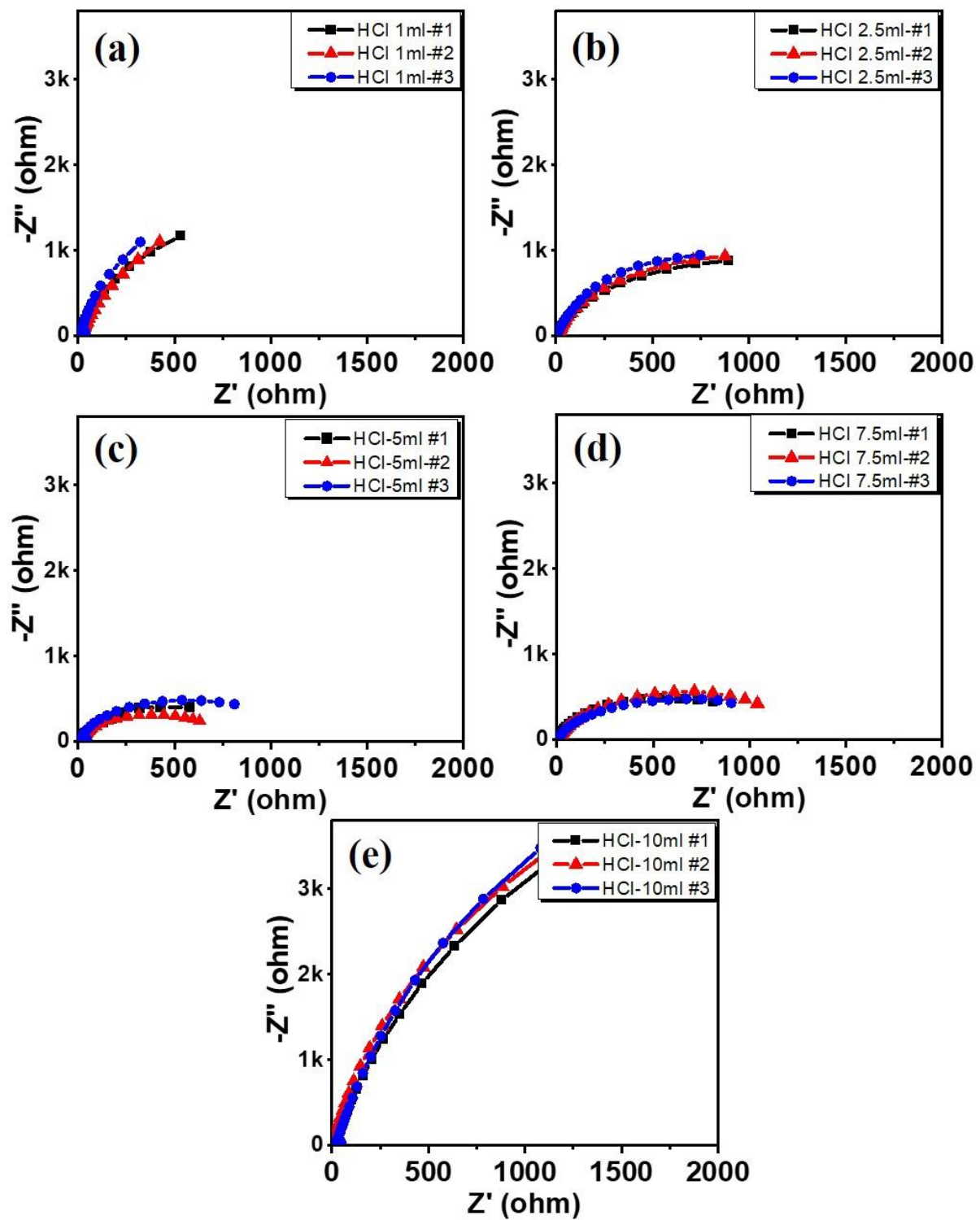
**Figure S3.** XRD spectra of the  $WO_3 \cdot nH_2O$  powders obtained by acid precipitation process with 2theta range from 10° to 70°. (a) HCl-1ml, (b) HCl-2.5ml, (c) HCl-5ml, (d) HCl-7.5ml, (e) HCl-10ml samples.



**Figure S4.** XRD spectra of the  $WO_3$  nanoplates grown on FTO glass with different HCl volume. (a) HCl-1ml, (b) HCl-2.5ml, (c) HCl-5ml, (d) HCl-7.5ml, (e) HCl-10ml samples.



**Figure S5.** LSV curves obtained from the WO<sub>3</sub> photoanodes under AM 1.5G condition. (a) HCl-1ml, (b) HCl-2.5ml, (c) HCl-5ml, (d) HCl-7.5ml, (e) HCl-10ml samples.



**Figure S6.** EIS Nyquist plots of all the photoanodes under AM 1.5G condition. (a) HCl-1ml, (b) HCl-2.5ml, (c) HCl-5ml, (d) HCl-7.5ml, (e) HCl-10ml samples.